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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of  
Toshikazu SEGAWA et al

531 Rec'd PCT

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S. N.  
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For: METHOD OF PRODUCING PHASE MASK FOR PROCESSING OPTICAL FIBER AND  
OPTICAL FIBER WITH BRAGG DIFFRACTION GRATING FABRICATED BY USING  
THE OPTICAL FIBER-PROCESSING PHASE MASK

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Please make the following amendments to this application  
prior to examination thereof:

In the Specification:

Page 10, lines 9-11, please replace this paragraph with the  
following:

Figs. 2(a) and 2(b) comprise diagrams showing an electron  
beam writing method used in the method of producing a phase mask,  
and also showing a section of the phase mask.

Page 10, lines 15-19, please replace these paragraphs with  
the following:

Figs. 4(a) through 4(h) are sectional views showing steps of  
an embodiment of the phase mask producing method according to the  
present invention.

Figs. 5(a) through 5(c) comprise diagrams for describing  
optical fiber processing and a phase mask used therefor.